



2019 EUVL Workshop - FIRST CALL FOR PAPERS

We are inviting presentations and poster papers for the 2019 EUVL Workshop, to be held June 10-13, 2019 at The Center for X-ray Optics (CXRO) at LBNL in Berkeley, CA. This workshop, now in its twelfth year, is focused on the fundamental science of EUV Lithography (EUVL) and its continued extension to support Moore's Law. A smaller group setting suitable for networking and brainstorming, with a focus on fundamentals, sets this conference apart from other larger conferences based on the commercial aspects of EUVL.

With EUVL scanners maturing and already in high-volume manufacturing to support the 7 nm node, the focus of workshop is now on infrastructure challenges for current and future nodes to be enabled by higher NA scanners. We also invite papers looking into options to extend EUVL beyond high NA. Technology review papers and presentations with innovative approaches are encouraged. Specific topics covered under this workshop include power scaling for high power sources, metrology sources, masks, optics, resist, contamination, metrology and patterning. A detailed list of topics for the 2019 EUVL workshop will be soon published on our website www.euvlitho.com.

The workshop will be preceded by an all-day EUV Lithography Short Course on June 10. Registration for the workshop begins on June 11, followed by presentations, panel discussions and a poster session on June 12 and 13. The keynote speakers for the workshop will be announced soon on our website www.euvlitho.com. The 2019 EUVL Workshop is co-organized by EUV Litho, Inc. and The Center for X-ray Optics (CXRO) at Lawrence Berkeley National Laboratory, Berkeley, CA.

Instructions for Submissions and Deadlines

Please submit abstracts of less than 200 words and indicate whether an oral or poster paper is preferred. Please also include each author's full name, e-mail address, affiliation and mailing address, together with a brief biography and photograph of the presenting author. Abstracts should be submitted via email to abstracts@euvlitho.com. **The deadline for abstract submission is March 22, 2019.** Travel and registration information will be available at our website by end of March 2019. For logistics related issues, please contact Meeting Services at info@euvlitho.com and for technical questions, please contact Vivek Bakshi (Chair) at vivek.bakshi@euvlitho.com or Patrick Naulleau (Co-Chair) at pnaulleau@lbl.gov.

Co-Organized by

